22. A process for manufacturing a liquid crystal display device according to claim 8, wherein the temperature of the substrate is maintained higher than room temperature and no greater than 80°C during irradiation of the polarized UV light to the orientation film formed on the substrate so as to facilitate optical orientation of the orientation film for the liquid crystal display device.

23. A process for manufacturing a liquid crystal display device according to claim 13, wherein the substrate is maintained at a temperature which is higher than room temperature and no greater than 80°C for a time period during the irradiation of polarized UV light to the orientation film formed on the substrate so as to facilitate optical orientation of the orientation film for the liquid display device.

24. A process for manufacturing a liquid crystal display device according to claim 18, wherein the substrate is heated at a temperature no greater than 80°C during irradiation of polarized UV light to the orientation film formed on the substrate so as to facilitate optical orientation of the orientation film of the liquid crystal display device.